



ISPlasma2018/IC-PLANTS2018

10th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials
11th International Conference on Plasma-Nano Technology & Science

March 4-8, 2018

Meijo University, Nagoya, Japan

Organizing Committee

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Sponsored by : The Japan Society of Applied Physics

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<http://www.isplasma.jp/>

※The photograph is an image.



Registration

Advanced Online Registration is required.

Registration Fee : Early Registration (Until Jan 31, 2018)

On-site Registration

Tutorial Fee : Participant in Main Symposium

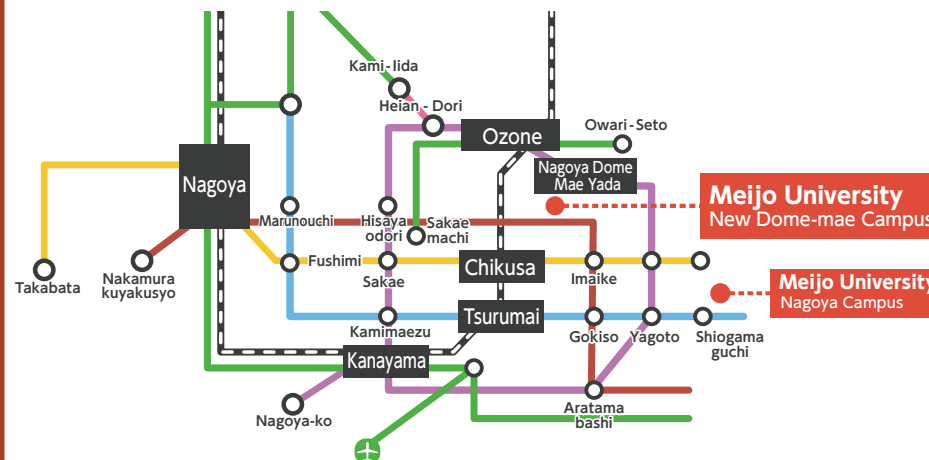
Tutorial Registration Only

Banquet Fee (on March 6, 2018)

	General	Student
Registration Fee : Early Registration (Until Jan 31, 2018)	JPY 45,000	JPY 15,000
On-site Registration	JPY 50,000	JPY 20,000
Tutorial Fee : Participant in Main Symposium	JPY 1,000	JPY 1,000
Tutorial Registration Only	JPY 10,000	JPY 5,000
Banquet Fee (on March 6, 2018)	JPY 6,000	JPY 3,000

* Refunds cannot be made at any reason.

Access



Meitetsu Airport Line Central Japan International Airport Station

26 min. by rapid train

Meitetsu Line Kanayama Station

Kanayama Station

8 min. by Train JR Chuo Line

21 min. by subway Meijo Line

Ozone Station

15 min. on foot

Nagoya Dome-mae Yada Station

5 min. on foot

Meijo University New Dome-mae Campus

Meijo University
New Dome-mae Campus

Meijo University
Nagoya Campus

Contact

Secretariat : Inter Group Corp.

E-mail : isplasma2018@intergroup.co.jp Website : <http://www.isplasma.jp/>

ISPlasma/IC-PLANTS is a specialized international symposium that brings together about 1,000 world-leading scientists and engineers in Nagoya, Japan to discuss latest researches in the fields of advanced plasma science, its applications for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. In this symposium biosensing technologies will be also highlighted, because of their increasing importance in healthcare, agri-food and environmental areas. We hope that this symposium will provide an ideal venue for the exchange of new ideas and information, and also support the initiation or further development of international collaborations among those who work in these multidisciplinary fields.

● Related Fields

Plasma Science & Technologies

- Plasma Source
- Modeling & Simulation
- Thin Film Deposition Process
- Flexible Electronics
- Plasma Agriculture
- Advanced Plasma Diagnostics
- Plasma in Liquid
- Etching Process
- Plasma Biology & Medicine
- Plasma for Nano & Green Technologies

Nitride Semiconductors

- Crystal Growth of GaN & Related Materials
- Characterization
- Optical & Optoelectronic Devices
- MBE Growth & Nitrogen Source
- Device Processing
- Electron & Power Devices

Nanomaterials

- Nanodots & Nanoparticles
- 2D Nanomaterials
- Composites & Functionally Graded Materials
- Applications for Energy
- Nanotubes, Nanowires & Nanorods
- Porous Materials & Membranes
- Surface Modification & Functionalization
- Nanomedicine & Sensing

Bio applications

- Detection Technologies
- Electrochemical Devices
- Biomarkers & Biosensor Surfaces
- Biomaterials
- Optical Devices, Bioimaging
- Biosensors
- Fabrication Technologies
- Biodevices, uTAS, Lab on a Chip

● Abstract Submission

Online abstract submission (one-page English) is available from <http://www.isplasma.jp/>
Submission Deadline : Monday, October 2, 2017 JST

● Special Issue

Selected papers will be published in a special issue of a scientific journal.

● Tutorial

Tutorial for Plasma Science, Nitride Semiconductors Nanomaterials and Biosensing will be held on Sun, March 4, 13:00

PROGRAM

Plenary Speakers

- I. Akasaki (Meijo University, JAPAN)
- S. Iijima (Meijo University JAPAN)

Keynote Speakers

- U. Czarnetzki (Ruhr-Universität Bochum, GERMANY)
- J. G. Han (Sungkyunkwan University, KOREA)

Invited Speakers

- J. W. Bradley (University Liverpool, UK)
- W. H. Chiang (National Taiwan University of Science and Technology, TAIWAN)
- Y. C. Chou (National Chiao Tung University, TAIWAN)
- S. Chowdhury (UC Davis, U.S.A)
- R. Dussart (University of Orleans, FRANCE)
- R. A. Ferreyra (Kyoto Institute of Technology, JAPAN)
- M. Gherardi (University of Bologna, ITALY)
- J. L. He (Feng Chia University, TAIWAN)
- S. Keller (University of California, Santa Barbara, U.S.A)
- S. Krukowski (Unipress, POLAND)
- K. Matsuda (Kyoto University, JAPAN)
- M. Nagatsu (Shizuoka University, JAPAN)
- K. Nakazato (Nagoya University, JAPAN)
- T. Nozaki (Tokyo Institute of Technology, JAPAN)
- Y. Saito (Nagoya University, JAPAN)
- T. Sugaya (AIST, JAPAN)
- F. Tochikubo (Tokyo Metropolitan University, JAPAN)
- X. L. Wang (AIST, JAPAN)
- C. H. Wang (National Taiwan University of Science & Technology, TAIWAN)
- H. Watanabe (Osaka University, JAPAN)
- K. Yamamura (Osaka University, JAPAN)
- H. Chae (Sungkyunkwan University, KOREA)
- G. Dinescu (University of Bucharest, ROMANIA)
- D. Feezell (The University of New Mexico, U.S.A)
- K. Fukuzawa (Nagoya University, JAPAN)
- S. Gortchakow (INP Greifswald, GERMANY)
- H. Kano (University of Tsukuba, JAPAN)
- J.F. Kolb (University Rostock, GERMANY)
- E. Martines (Consorzio RFX, ITALY)
- K. Nagashio (The University of Tokyo, JAPAN)
- Y. Nakatsu (Kyushu University, JAPAN)
- K. Nojiri (Lam Research Corp., JAPAN)
- D. Rafalsky (Ecole Polytechnique, FRANCE)
- M. Shiratani (Kyushu University, JAPAN)
- N. Tansu (Lehigh University, U.S.A)
- J. P. Trelles (University of Massachusetts Lowell, U.S.A)
- T. C. Wei (Chung Yuan Cristian University, TAIWAN)
- L. W. Yu (Nanjing University, CHINA)

Tutorial Speakers

- P. Chabert (LPP,CNRS,Ecole Polytechnique, FRANCE)
- Y. Nanishi (Ritsumeikan University, JAPAN)
- P. Favia (University of Bari, ITALY)
- Y. Saito (Nagoya University, JAPAN)
- H. Sakakita (AIST, JAPAN)